

The documentation and process conversion measures necessary to comply with this revision shall be completed by 21 September 2013.

INCH-POUND

MIL-PRF-19500/663F  
21 June 2013  
SUPERSEDING  
MIL-PRF-19500/663E  
23 February 2013

PERFORMANCE SPECIFICATION SHEET

SEMICONDUCTOR DEVICE, FIELD EFFECT RADIATION HARDENED TRANSISTORS,  
N-CHANNEL, SILICON, TYPES 2N7431, 2N7432, AND 2N7433,  
JANTXVR, F, G, AND H; AND JANSR, F, G, AND H

This specification is approved for use by all Departments and Agencies of the Department of Defense.

The requirements for acquiring the product described herein shall consist of this specification sheet and [MIL-PRF-19500](#).

1. SCOPE

1.1 Scope. This specification covers the performance requirements for an N-channel, enhancement-mode, MOSFET, radiation hardened, power transistor. Two levels of product assurance are provided for each device type specified in [MIL-PRF-19500](#), with avalanche energy maximum rating (E<sub>AS</sub>) and maximum avalanche current (I<sub>AS</sub>). See 6.5 for JANHC and JANKC die versions.

1.2 Physical dimensions. See [figure 1](#), TO-254AA.

1.3 Maximum ratings. Unless otherwise specified, T<sub>C</sub> = +25°C.

Type	P <sub>T</sub> (1) T <sub>C</sub> = +25°C	P <sub>T</sub> T <sub>A</sub> = +25°C	R <sub>θJC</sub> (2)	V <sub>DS</sub>	V <sub>DG</sub>	V <sub>GS</sub>	I <sub>D1</sub> (3) (4)	I <sub>D2</sub> T <sub>C</sub> = +100°C (3) (4)	I <sub>S</sub>	I <sub>DM</sub>	T <sub>J</sub> and T <sub>STG</sub>
	<u>W</u>	<u>W</u>	<u>°C/W</u>	<u>V<sub>dc</sub></u>	<u>V<sub>dc</sub></u>	<u>V<sub>dc</sub></u>	<u>A<sub>dc</sub></u>	<u>A<sub>dc</sub></u>	<u>A<sub>dc</sub></u>	<u>A(pk)</u>	<u>°C</u>
2N7431	250	3.0	0.5	60	60	±20	35.0	35.0	35.0	140	-55
2N7432	250	3.0	0.5	100	100	±20	35.0	35.0	35.0	140	to
2N7433	250	3.0	0.5	200	200	±20	35.0	25.0	35.0	140	+150

(1) Derate linearly by 2.0 W/°C for T<sub>C</sub> > +25°C.

(2) See [figure 2](#), thermal impedance curves.

(3) The following formula derives the maximum theoretical I<sub>D</sub> limit. I<sub>D</sub> is limited by package and internal wires and may be limited by pin diameter:

$$I_D = \sqrt{\frac{T_{JM} - T_C}{(R_{\theta JC}) \times (R_{DS(on)} \text{ at } T_{JM})}}$$

(4) See [figure 3](#), maximum drain current graph.

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1.4 Primary electrical characteristics at T<sub>c</sub> = +25°C.

Type	Min V <sub>(BR)DSS</sub> V <sub>GS</sub> = 0 I <sub>D</sub> = 1.0 mA dc	V <sub>GS(TH)1</sub> V <sub>DS</sub> ≥ V <sub>GS</sub> I <sub>D</sub> = 1.0 mA dc		Max I <sub>DSS1</sub> V <sub>GS</sub> = 0 V <sub>DS</sub> = 80 percent of rated V <sub>DS</sub>	Max r <sub>DS(ON)</sub> (1) V <sub>GS</sub> = 12 V dc		EAS at I <sub>D1</sub>	I <sub>AS</sub>
					T <sub>J</sub> = +25°C at I <sub>D2</sub>	T <sub>J</sub> = +150°C at I <sub>D2</sub>		
	V dc	V dc		μA dc	ohm	ohm	mJ	A
		Min	Max					
2N7431	60	2.0	4.0	25	0.021	0.040	500	35.0
2N7432	100	2.0	4.0	25	0.045	0.105	500	35.0
2N7433	200	2.0	4.0	25	0.070	0.175	500	35.0

(1) Pulsed (see 4.5.1).

2. APPLICABLE DOCUMENTS

2.1 General. The documents listed in this section are specified in sections 3, 4, or 5 of this specification. This section does not include documents cited in other sections of this specification or recommended for additional information or as examples. While every effort has been made to ensure the completeness of this list, document users are cautioned that they must meet all specified requirements of documents cited in sections 3, 4, or 5 of this specification, whether or not they are listed.

2.2 Government documents.

2.2.1 Specifications, standards, and handbooks. The following specifications, standards, and handbooks form a part of this document to the extent specified herein. Unless otherwise specified, the issues of these documents are those cited in the solicitation or contract.

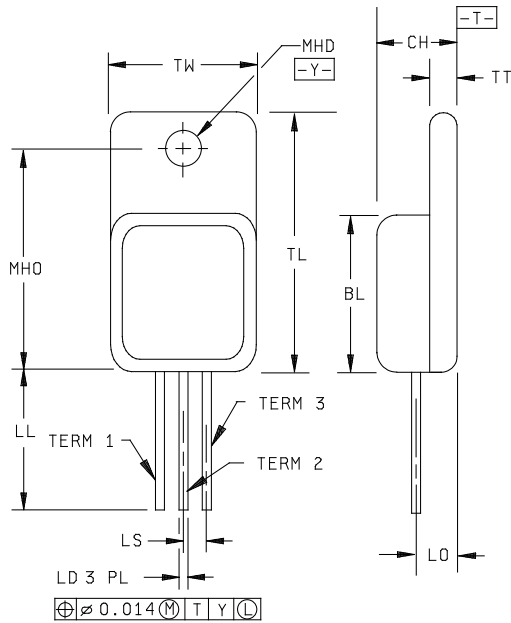
[MIL-PRF-19500](#) - Semiconductor Devices, General Specification for.

DEPARTMENT OF DEFENSE STANDARDS

[MIL-STD-750](#) - Test Methods for Semiconductor Devices.

\* (Copies of these documents are available online at <http://quicksearch.dla.mil> or <https://assist.dla.mil> or from the Standardization Document Order Desk, 700 Robbins Avenue, Building 4D, Philadelphia, PA 19111-5094.)

2.3 Order of precedence. Unless otherwise noted herein or in the contract, in the event of a conflict between the text of this document and the references cited herein, the text of this document takes precedence. Nothing in this document, however, supersedes applicable laws and regulations unless a specific exemption has been obtained.



Ltr	Dimensions				Notes
	Inches		Millimeters		
	Min	Max	Min	Max	
BL	.535	.545	13.59	13.84	
CH	.249	.260	6.32	6.60	
LD	.035	.045	0.89	1.14	
LL	.510	.570	12.95	14.48	3
LO	.150 BSC		3.81 BSC		
LS	.150 BSC		3.81 BSC		
MHD	.139	.149	3.53	3.78	
MHO	.665	.685	16.89	17.40	
TL	.790	.800	20.07	20.32	4
TT	.040	.050	1.02	1.27	
TW	.535	.545	13.59	13.84	4
Term 1	Drain				
Term 2	Source				
Term 3	Gate				

NOTES:

1. Dimensions are in inches.
2. Millimeters are given for general information only.
3. Protrusion thickness of ceramic eyelets included in dimension LL.
4. All terminals are isolated from case.
5. In accordance with ASME Y14.5M, diameters are equivalent to  $\phi x$  symbology.

FIGURE 1. Physical dimensions for TO-254AA.

### 3. REQUIREMENTS

3.1 General. The individual item requirements shall be as specified in [MIL-PRF-19500](#) and as modified herein.

3.2 Qualification. Devices furnished under this specification shall be products that are manufactured by a manufacturer authorized by the qualifying activity for listing on the applicable qualified manufacturer's list (QML) before contract award (see [4.2](#) and [6.3](#)).

3.3 Abbreviations, symbols, and definitions. Abbreviations, symbols, and definitions used herein shall be as specified in [MIL-PRF-19500](#) and as follows.

$I_{AS}$  ..... Rated avalanche current, nonrepetitive  
nC ..... nano Coulomb.

3.4 Interface and physical dimensions. The Interface and physical dimensions shall be as specified in [MIL-PRF-19500](#), [figure 1](#) (TO-254AA) herein. Methods used for electrical isolation of the terminals shall employ materials that contain a minimum of 90 percent  $Al_2O_3$  (ceramic).

3.4.1 Lead formation and finish. Lead finish shall be solderable in accordance with [MIL-STD-750](#), [MIL-PRF-19500](#) and herein. Where a choice of finish is desired, it shall be specified in the acquisition document (see [6.2](#)). When lead formation is performed, as a minimum, the vendor shall perform 100 percent hermetic seal in accordance with screen 14 of [MIL-PRF-19500](#) and 100 percent dc testing in accordance with [table I](#), subgroup 2 herein.

3.4.2 Internal construction. Multiple chip construction is not permitted in this specification.

3.5 Marking. Marking shall be in accordance with [MIL-PRF-19500](#). At the option of the manufacturer, marking of the country of origin may be omitted from the body of the transistor but shall be retained on the initial container.

3.6 Electrical performance characteristics. Unless otherwise specified herein, the electrical performance characteristics are as specified in [1.3](#), [1.4](#), and [table I](#).

3.7 Electrostatic discharge protection. The devices covered by this specification require electrostatic discharge protection.

3.7.1 Handling. MOS devices must be handled with certain precautions to avoid damage due to the accumulation of static charge. However, the following handling practices are recommended (see [3.7](#)).

- \* a. Devices shall be handled on benches with conductive handling devices.
- b. Ground test equipment, tools, and personnel handling devices.
- c. Do not handle devices by the leads.
- d. Store devices in conductive foam or carriers.
- e. Avoid use of plastic, rubber, or silk in MOS areas.
- f. Maintain relative humidity above 50 percent if practical.
- g. Care should be exercised during test and troubleshooting to apply not more than maximum rated voltage to any lead.
- h. Gate must be terminated to source,  $R \leq 100 \text{ k}\Omega$ , whenever bias voltage is to be applied drain to source.

3.8 Electrical test requirements. The electrical test requirements shall be as specified in [table I](#).

3.9 Workmanship. Semiconductor devices shall be processed in such a manner as to be uniform in quality and shall be free from other defects that will affect life, serviceability, or appearance.

#### 4. VERIFICATION

4.1 Classification of inspections. The inspection requirements specified herein are classified as follows:

- a. Qualification inspection (see 4.2).
- b. Screening (see 4.3).
- c. Conformance inspection (see 4.4 and tables I and II).

4.2 Qualification inspection. Qualification inspection shall be in accordance with MIL-PRF-19500.

4.2.1 Group E qualification. Group E inspection shall be performed for qualification or re-qualification only. In case qualification was awarded to a prior revision of the specification sheet that did not request the performance of table III tests, the tests specified in table III herein that were not performed in the prior revision shall be performed on the first inspection lot of this revision to maintain qualification.

4.2.1.1 Single event effects (SEE). SEE shall be performed at initial qualification and after process or design changes which may affect radiation hardness (see table III and table IV). Upon qualification, manufacturers shall provide the verification test conditions from section 5 of method 1080 of MIL-STD-750 that were used to qualify the device for inclusion into section 6 of the slash sheet. End-point measurements shall be in accordance with table II. SEE characterization data shall be made available upon request of the qualifying or acquiring activity.

\* 4.3 Screening (JANS and JANTXV levels only). Screening shall be in accordance with table E-IV of MIL-PRF-19500 and as specified herein. The following measurements shall be made in accordance with table I herein. Devices that exceed the limits of table I herein shall not be acceptable.

Screen (see table E-IV of MIL-PRF-19500) (1) (2)	Measurement	
	JANS level	JANTXV levels
(3)	Gate stress test (see 4.3.1)	Gate stress test (see 4.3.1)
(3)	Method 3470 of MIL-STD-750, E <sub>AS</sub> (see 4.3.2)	Method 3470 of MIL-STD-750, E <sub>AS</sub> (see 4.3.2)
(3) 3c	Method 3161 of MIL-STD-750, thermal impedance, (see 4.3.3)	Method 3161 of MIL-STD-750, thermal impedance, (see 4.3.3)
9	Subgroup 2 of table I herein I <sub>DSS1</sub> , I <sub>GSSF1</sub> , I <sub>GSSR1</sub>	Not applicable
10	Method 1042 of MIL-STD-750, test condition B	Method 1042 of MIL-STD-750, test condition B
11	I <sub>GSSF1</sub> , I <sub>GSSR1</sub> , I <sub>DSS1</sub> , r <sub>DS(ON)1</sub> , V <sub>GS(TH)1</sub> , subgroup 2 of table I herein. $\Delta I_{GSSF1} = \pm 20$ nA dc or $\pm 100$ percent of initial value, whichever is greater. $\Delta I_{GSSR1} = \pm 20$ nA dc or $\pm 100$ percent of initial value, whichever is greater. $\Delta I_{DSS1} = \pm 10$ $\mu$ A dc or $\pm 100$ percent of initial value, whichever is greater.	I <sub>GSSF1</sub> , I <sub>GSSR1</sub> , I <sub>DSS1</sub> , r <sub>DS(ON)1</sub> , V <sub>GS(TH)1</sub> , subgroup 2 of table I herein.
12	Method 1042 of MIL-STD-750, test condition A	Method 1042 of MIL-STD-750, test condition A
13	Subgroups 2 and 3 of table I herein. $\Delta I_{GSSF1} = \pm 20$ nA dc or $\pm 100$ percent of initial value, whichever is greater. $\Delta I_{GSSR1} = \pm 20$ nA dc or $\pm 100$ percent of initial value, whichever is greater. $\Delta I_{DSS1} = \pm 10$ $\mu$ A dc or $\pm 100$ percent of initial value, whichever is greater. $\Delta r_{DS(ON)1} = \pm 20$ percent of initial value. $\Delta V_{GS(TH)1} = \pm 20$ percent of initial value.	Subgroups 2 and 3 of table I herein. $\Delta I_{GSSF1} = \pm 20$ nA dc or $\pm 100$ percent of initial value, whichever is greater. $\Delta I_{GSSR1} = \pm 20$ nA dc or $\pm 100$ percent of initial value, whichever is greater. $\Delta I_{DSS1} = \pm 10$ $\mu$ A dc or $\pm 100$ percent of initial value, whichever is greater. $\Delta r_{DS(ON)1} = \pm 20$ percent of initial value. $\Delta V_{GS(TH)1} = \pm 20$ percent of initial value.
* 17	Method 1081 of MIL-STD-750 (see 4.3.4), Endpoints: Subgroup 2 of table I herein.	Method 1081 of MIL-STD-750 (see 4.3.4), Endpoints: Subgroup 2 of table I herein.

- (1) At the end of the test program, I<sub>GSSF1</sub>, I<sub>GSSR1</sub>, and I<sub>DSS1</sub> are measured.
- (2) An out-of-family program to characterize I<sub>GSSF1</sub>, I<sub>GSSR1</sub>, I<sub>DSS1</sub>, and V<sub>GS(th)1</sub> shall be invoked.
- (3) Shall be performed anytime after temperature cycling, screen 3a; JANTXV level does not need to be repeated in screening requirements.

4.3.1 Gate stress test. Apply  $V_{GS} = 30$  V minimum for  $t = 250$   $\mu$ s minimum.

4.3.2 Single pulse avalanche energy  $E_{AS}$ .

- a. Peak current ( $I_{AS}$ ) .....  $I_{AS} = I_{D1}$ .
- b. Peak gate voltage ( $V_{GS}$ )..... 12 V.
- c. Gate to source resistor ( $R_{GS}$ ).....  $25\Omega \leq R_{GS} \leq 200\Omega$ .
- d. Initial case temperature ( $T_C$ ) .....  $+25^\circ\text{C}$   $+10^\circ\text{C}$ ,  $-5^\circ\text{C}$ .
- e. Inductance .....  $L = (2E_{AS}/(I_{D1})^2) * ((V_{BR}-V_{DD})/V_{BR})$  mH minimum.
- f. Number of pulses to be applied ..... 1 pulse minimum.
- g. Supply voltage ( $V_{DD}$ ) ..... 25 V (50 V for 2N7433).

4.3.3 Thermal impedance. The thermal impedance measurements shall be performed in accordance with method 3161 of [MIL-STD-750](#) using the guidelines in that method for determining  $I_M$ ,  $I_H$ ,  $t_H$ ,  $t_{SW}$ , (and  $V_H$  where appropriate). Measurement delay time ( $t_{MD}$ ) = 70  $\mu$ s max. See [table III](#), group E, subgroup 4 herein.

\* 4.3.4 Dielectric withstanding voltage.

- a. Magnitude of test voltage.....900 V dc.
- b. Duration of application of test voltage.....15 seconds (min).
- c. Points of application of test voltage.....All leads to case (bunch connection).
- d. Method of connection.....Mechanical.
- e. Kilovolt-ampere rating of high voltage source.....1,200V /1.0 mA (min).
- f. Maximum leakage current.....1.0 mA.
- g. Voltage ramp up time.....500V /second.

4.4 Conformance inspection. Conformance inspection shall be in accordance with [MIL-PRF-19500](#), and as specified herein.

4.4.1 Group A inspection. Group A inspection shall be conducted in accordance with table E-V of [MIL-PRF-19500](#) and [table I](#) herein. End-point electrical measurements shall be in accordance with [table I](#), subgroup 2 herein.

4.4.2 Group B inspection. Group B inspection shall be conducted in accordance with the conditions specified for subgroup testing in table E-VIA (JANS) and table E-VIB (JANTXV) of [MIL-PRF-19500](#), and herein. End-point electrical measurements shall be in accordance with [table I](#), subgroup 2 herein.

\* 4.4.2.1 Group B inspection, table E-VIA (JANS) of MIL-PRF-19500.

<u>Subgroup</u>	<u>Method</u>	<u>Condition</u>
B3	1051	Test condition G, 100 cycles.
B3	2075	See 3.4.2.
B3	2077	SEM qualification may be performed anytime prior to lot formation.
* B4	1042	Test condition D. The heating cycle shall be 30 seconds minimum.
B5	1042	Accelerated steady-state gate bias, condition B, $V_{GS} = \text{rated}$ , $T_A = +175^\circ\text{C}$ , $t = 24$ hours minimum.
B5	1042	Accelerated steady-state reverse bias, condition A, $V_{DS} = \text{rated}$ , $T_A = +175^\circ\text{C}$ , $t = 120$ hours minimum.
B5	2037	Bond strength; test condition D.

4.4.2.2 Group B inspection, table E-VIB (JANTXV) of MIL-PRF-19500.

<u>Subgroup</u>	<u>Method</u>	<u>Condition</u>
B2	1051	Test condition G, 25 cycles.
B3	1042	Test condition D, 2,000 cycles. The heating cycle shall be 30 seconds minimum.
B3	2037	Test condition D. All internal bond wires for each device shall be pulled separately.

\* 4.4.3 Group C inspection. Group C inspection shall be conducted in accordance with the conditions specified for subgroup testing in table E-VII of MIL-PRF-19500 and as follows. Electrical measurements (end-points) shall be in accordance with the applicable of table I, subgroup 2 herein.

<u>Subgroup</u>	<u>Method</u>	<u>Condition</u>
C2	2036	Test condition A, weight = 10 pounds; $t = 15$ s.
C5	3161	See 4.3.3, $R_{\theta JC(\text{max})} = 0.50^\circ\text{C/W}$ .
* C6	1042	Test condition D. The heating cycle shall be 30 seconds minimum.

4.4.4 Group D Inspection. Group D inspection shall be conducted in accordance with table E-VIII of MIL-PRF-19500 and table II herein.

4.4.5 Group E inspection. Group E inspection shall be conducted in accordance with the conditions specified for subgroup testing in table E-IX of MIL-PRF-19500 and as specified in table III herein. Electrical measurements (end-points) shall be in accordance with table I, subgroup 2 herein.

4.5 Methods of inspection. Methods of inspection shall be as specified in the appropriate tables and as follows.

4.5.1 Pulse measurements. Conditions for pulse measurement shall be as specified in section 4 of MIL-STD-750.



TABLE I. Group A inspection.

Inspection <u>1/</u>	MIL-STD-750		Symbol	Limits		Unit
	Method	Conditions		Min	Max	
<u>Subgroup 1</u>						
Visual and mechanical inspection	2071					
<u>Subgroup 2</u>						
Thermal impedance <u>2/</u>	3161	See 4.3.3	$Z_{\theta JC}$			$^{\circ}C/W$
Breakdown voltage, drain to source	3407	$V_{GS} = 0\text{ V}$ , $I_D = 1\text{ mA dc}$ , bias condition C	$V_{(BR)DSS}$			
2N7431				60		V dc
2N7432				100		V dc
2N7433				200		V dc
Gate to source voltage threshold	3403	$V_{DS} \geq V_{GS}$ , $I_D = 1\text{ mA dc}$	$V_{GS(TH)1}$	2.0	4.0	V dc
Gate current	3411	$V_{GS} = +20\text{ V dc}$ , bias condition C, $V_{DS} = 0$	$I_{GSSF1}$		+ 100	nA dc
Gate current	3411	$V_{GS} = -20\text{ V dc}$ , bias condition C, $V_{DS} = 0$	$I_{GSSR1}$		- 100	nA dc
Drain current	3413	$V_{GS} = 0\text{ V dc}$ , Bias condition C $V_{DS} = 80\text{ percent of rated }V_{DS}$	$I_{DSS1}$		25	$\mu\text{A dc}$
Static drain to source on-state resistance	3421	$V_{GS} = 12\text{ V dc}$ , condition A pulsed (see 4.5.1), $I_D = I_{D2}$	$r_{DS(on)1}$			
2N7431					0.021	ohm
2N7432					0.045	ohm
2N7433					0.070	ohm
Static drain to source on-state resistance	3421	$V_{GS} = 12\text{ V dc}$ , condition A pulsed (see 4.5.1), $I_D = I_{D1}$	$r_{DS(on)2}$			
2N7431					0.021	ohm
2N7432					0.045	ohm
2N7433					0.077	ohm
Forward voltage	4011	Pulsed (see 4.5.1), $I_D = I_{D1}$ , $V_{GS} = 0\text{ V dc}$	$V_{SD}$			
2N7431					1.5	V dc
2N7432					1.8	V dc
2N7433					1.8	V dc

See footnotes at end of table.

TABLE I. Group A inspection - Continued.

Inspection 1/	MIL-STD-750		Symbol	Limits		Unit
	Method	Conditions		Min	Max	
<u>Subgroup 3</u>						
High temperature operation:						
Gate current	3411	$T_C = T_J = +125^\circ\text{C}$ $V_{GS} = +20$ and $-20$ V dc, bias condition C, $V_{DS} = 0$	$I_{GSS2}$		$\pm 200$	nA dc
Drain current	3413	$V_{GS} = 0$ V; bias condition C, $V_{DS} = 80$ percent of rated $V_{DS}$	$I_{DSS2}$		0.25	mA dc
Static drain to source on-state resistance	3421	$V_{GS} = 12$ V dc, condition A pulsed (see 4.5.1), $I_D = I_{D2}$	$r_{DS(on)3}$			
2N7431					0.034	ohm
2N7432					0.089	ohm
2N7433					0.140	ohm
Gate to source voltage (threshold)	3403	$V_{DS} \geq V_{GS}$ , $I_D = 1$ mA dc	$V_{GS(TH)2}$	1.0		V dc
Low temperature operation:						
Gate to source voltage (threshold)	3403	$V_{DS} \geq V_{GS}$ , $I_D = 1$ mA dc	$V_{GS(TH)3}$		5.0	V dc
<u>Subgroup 4</u>						
Forward transconductance	3475	$I_D = \text{rated } I_{D2}$ , $V_{DD} = 15$ V (see 4.5.1)	$g_{FS}$			
2N7431				18		S
2N7432				16		S
2N7433				9		S
Switching time test	3472	$I_D = I_{D1}$ , $V_{GS} = 12$ V dc, $R_G = 2.35 \Omega$ , $V_{DD} = 50$ percent of rated $V_{DS}$				
Turn-on delay time			$t_{d(on)}$			
2N7431					27	ns
2N7432					35	ns
2N7433					50	ns
Rise time			$t_r$			
2N7431					120	ns
2N7432					150	ns
2N7433					200	ns
Turn-off delay time			$t_{d(off)}$			
2N7431					120	ns
2N7432					150	ns
2N7433					200	ns

See footnotes at end of table.

TABLE I. Group A inspection - Continued.

Inspection <u>1/</u>	MIL-STD-750		Symbol	Limits		Unit
	Method	Conditions		Min	Max	
<u>Subgroup 4</u> - Continued						
Fall time 2N7431 2N7432 2N7433			$t_f$		100 130 130	ns ns ns
<u>Subgroup 5</u>						
Safe operating area test (high voltage)	3474	See figures 4, 5, and 6; $t_p = 10$ ms minimum, $V_{DS} = 80$ percent of maximum rated $V_{DS}$ , ( $V_{DS} \leq 200$ )				
Electrical measurements		See table I, subgroup 2				
<u>Subgroup 6</u>						
Not applicable						
<u>Subgroup 7</u>						
Gate charge	3471	Condition B				
On-state gate charge 2N7431 2N7432 2N7433			$Q_{g(on)}$		270 310 290	nC nC nC
Gate to source charge 2N7431 2N7432 2N7433			$Q_{gs}$		60 53 42	nC nC nC
Gate to drain charge 2N7431 2N7432 2N7433			$Q_{gd}$		110 110 120	nC nC nC
Reverse recovery time  2N7431 2N7432 2N7433	3473	$di/dt \leq 100$ A/ $\mu$ s, $V_{DD} \leq 50$ V, condition A. $I_D = I_{D1}$	$t_{rr}$		360 520 820	ns ns ns

1/ For sampling plan, see MIL-PRF-19500.

2/ This test required for the following end-point measurements only:  
Group B, subgroups 3 and 4 (JANS).  
Group B, subgroups 2 and 3 (JANTXV).  
Group C, subgroups 2 and 6.  
Group E, subgroup 1.

TABLE II. Group D inspection.

Inspection 1/ 2/ 3/	MIL-STD-750		Symbol	Pre-irradiation limits				Post-irradiation limits				Unit
	Method	Conditions		R		F, G, and H 4/		R		F, G, and H 4/		
				Min	Max	Min	Max	Min	Max	Min	Max	
<u>Subgroup 1</u>												
Not applicable												
<u>Subgroup 2</u>		TC = +25°C										
Steady-state total dose irradiation ( $V_{GS}$ bias) 5/	1019	$V_{GS} = 12\text{ V}$ , $V_{DS} = 0$										
Steady-state total dose irradiation ( $V_{DS}$ bias) 5/	1019	$V_{DS} = 80$ percent of rated $V_{DS}$ (pre-irradiation) $V_{GS} = 0$										
Pre and post electricals:												
Breakdown voltage, drain to source	3407	Bias condition C, $V_{DS} = 0$ , $I_D = 1\text{ mA}$	$V_{(BR)DSS}$									
2N7431				60		60		60		60		V dc
2N7432				100		100		100		100		V dc
2N7433				200		200		200		200		V dc
Gate to source voltage (threshold)	3403	$V_{DS} \geq V_{GS}$	$V_{GS(th)1}$									
2N7431				2.0	4.0	2.0	4.0	2.0	4.0	1.25	4.5	V dc
2N7432				2.0	4.0	2.0	4.0	2.0	4.0	1.25	4.5	V dc
2N7433				2.0	4.0	2.0	4.0	2.0	4.0	1.25	4.5	V dc
Gate current	3411	Bias condition C, $V_{GS} = 20\text{ V}$ , $V_{DS} = 0$	$I_{GSSF1}$		100		100		100		100	nA dc
Gate current	3411	Bias condition C, $V_{GS} = -20\text{ V}$ , $V_{DS} = 0$	$I_{GSSR1}$		-100		-100		-100		-100	nA dc
Drain current	3413	Bias condition C, $V_{GS} = 0$ , $V_{DS} = 80$ percent of rated $V_{DS}$ (pre-irradiation)	$I_{DSS1}$		25		25		25		50	$\mu\text{A}$ dc

See footnotes at end of table.

TABLE II. Group D inspection - Continued.

Inspection <u>1/</u> <u>2/</u> <u>3/</u>	MIL-STD-750		Symbol	Pre-irradiation limits				Post-irradiation limits				Unit
	Method	Conditions		R		F, G, and H <u>4/</u>		R		F, G, and H <u>4/</u>		
				Min	Max	Min	Max	Min	Max	Min	Max	
Static drain to source on-state voltage	3405	$V_{GS} = 12\text{ V}$ , condition A, pulsed (see 4.5.1), $I_D = I_{D2}$	$V_{DS(on)1}$									
2N7431				.735	.735	.735	1.050	V dc				
2N7432				1.575	1.575	1.575	2.170	V dc				
2N7433	1.750	1.750	1.750	2.750	V dc							
Forward voltage source to drain diode	4011	$V_{GS} = 0$ , $I_D = I_{D1}$	$V_{SD}$									
2N7431				1.5	1.5	1.5	1.5	V dc				
2N7432				1.8	1.8	1.8	1.8	V dc				
2N7433	1.8	1.8	1.8	1.8	V dc							

1/ For sampling plan see MIL-PRF-19500.

2/ Group D qualification may be performed prior to lot formation. Wafers qualified to these group D QCI requirements may be used for any other specification sheet utilizing the same die design.

3/ At the manufacturer's option, group D samples need not be subjected to the screening tests, and may be assembled in its qualified package or in any qualified package that the manufacturer has data to correlate the performance to the designated package.

4/ The H designation represents devices which pass end-points at all R, F, G, and H designated total-ionizing-dose (TID) levels.

5/ Separate samples shall be pulled for each bias.

TABLE III. Group E inspection (all quality levels) for qualification or re-qualification only.

Inspection	MIL-STD-750		Sample plan
	Method	Conditions	
<u>Subgroup 1</u>			45 devices c = 0
Temperature cycling	1051	Condition G, 500 cycles	
Hermetic seal	1071		
Fine leak			
Gross leak			
Electrical measurements		See <a href="#">table I</a> , subgroup 2	
<u>Subgroup 2 1/</u>			45 devices c = 0
Steady-state reverse bias	1042	Condition A, 1,000 hours	
Electrical measurements		See <a href="#">table I</a> , subgroup 2	
Steady-state gate bias	1042	Condition B, 1,000 hours	
Electrical measurements		See <a href="#">table I</a> , subgroup 2	
<u>Subgroup 4</u>			Sample size N/A
Thermal impedance curves		See <a href="#">MIL-PRF-19500</a> .	
<u>Subgroup 10</u>			22 devices c = 0
Commutating diode for safe operating area test procedure for measuring dv/dt during reverse recovery of power MOSFET transistors or insulated gate bipolar transistors	3476	Test conditions shall be derived by the manufacturer	
<u>Subgroup 11</u>			
SEE <a href="#">2/</a> <a href="#">3/</a>	1080	See <a href="#">MIL-STD-750</a> method 1080 and <a href="#">6.2</a> .	

1/ A separate sample for each test shall be pulled.

2/ Group E qualification of SEE effect testing may be performed prior to lot formation. Qualification may be extended to other specification sheets utilizing the same structurally identical die design.

3/ Device qualification to a higher level LET is sufficient to qualify all lower level LETs

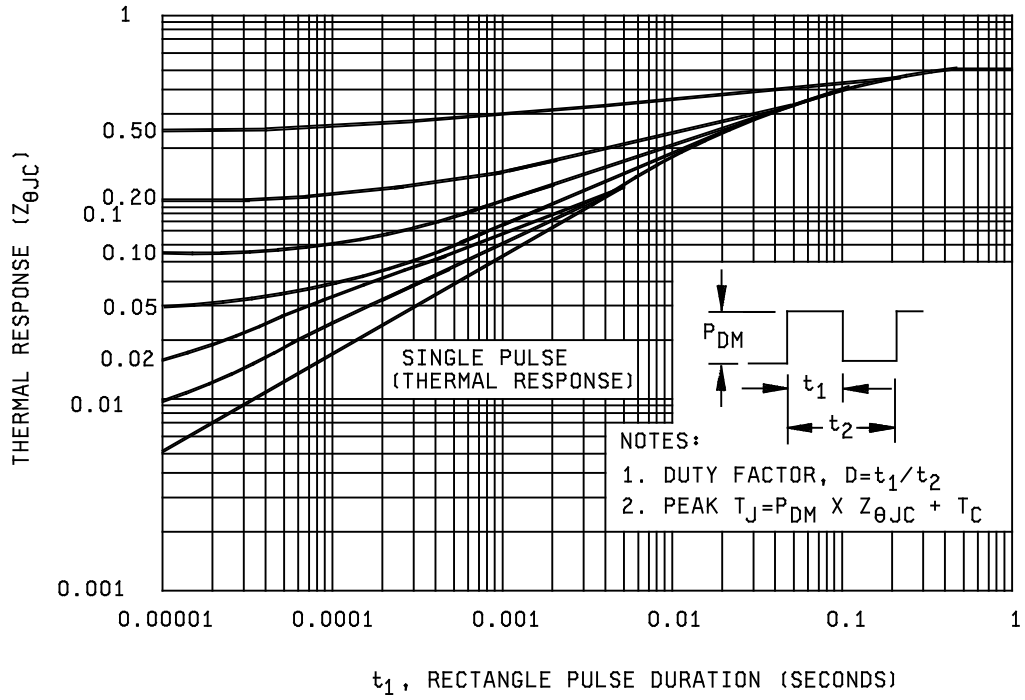
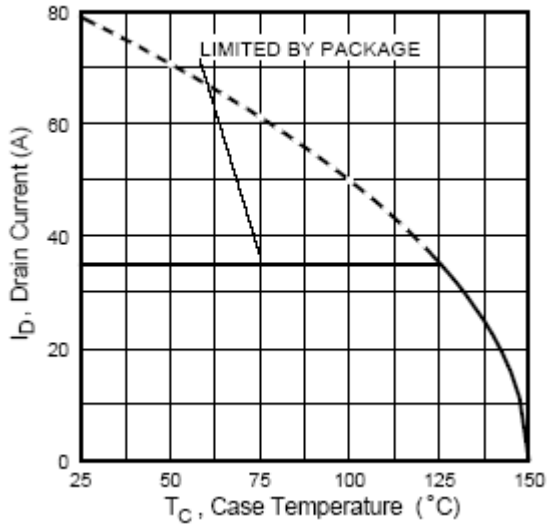
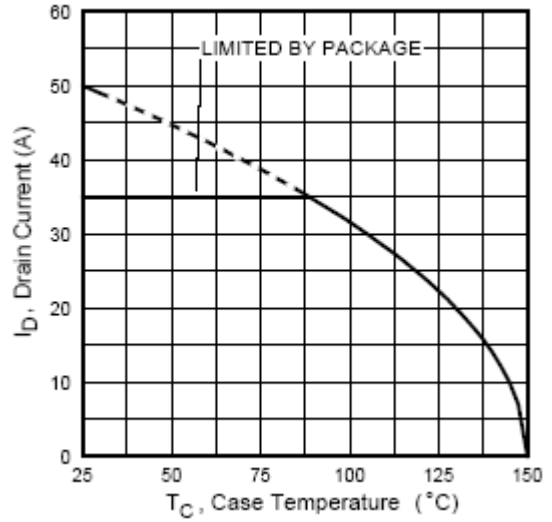


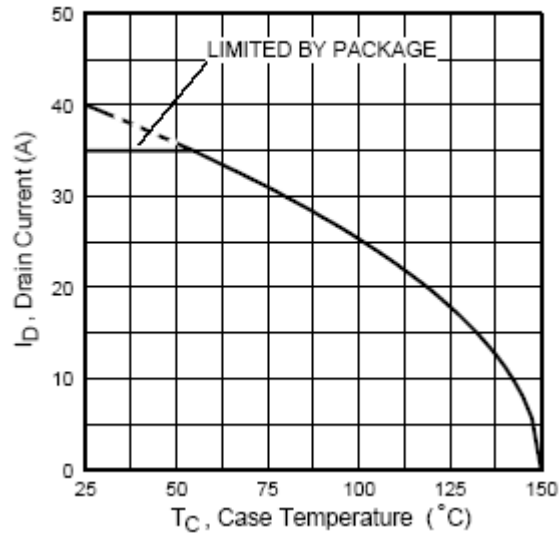
FIGURE 2. Thermal impedance curves.



2N7431



2N7432



2N7433

FIGURE 3. Maximum drain current versus case temperature graph (all devices).



2N7431

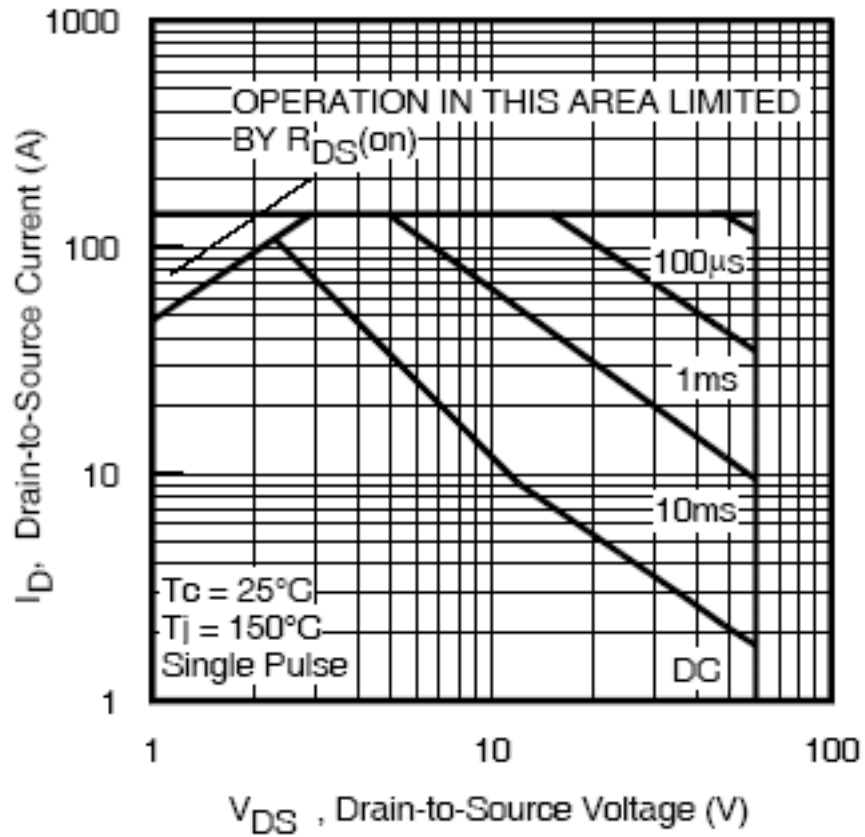


FIGURE 4. Safe operating area graph.

2N7432

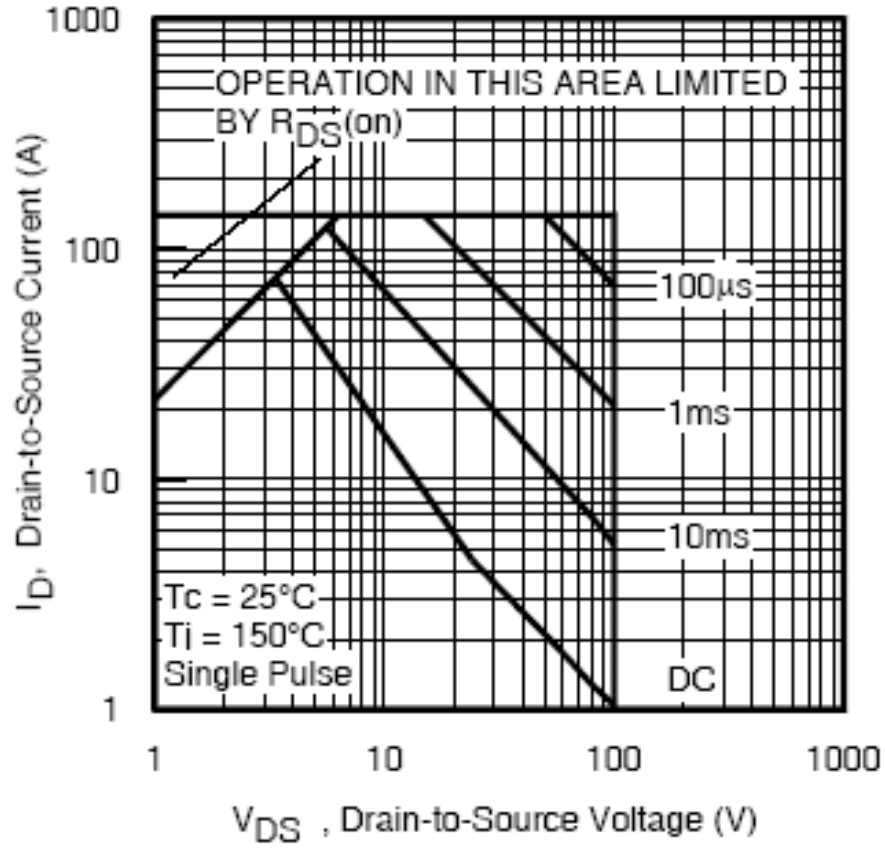


FIGURE 5. Safe operating area graph.

2N7433

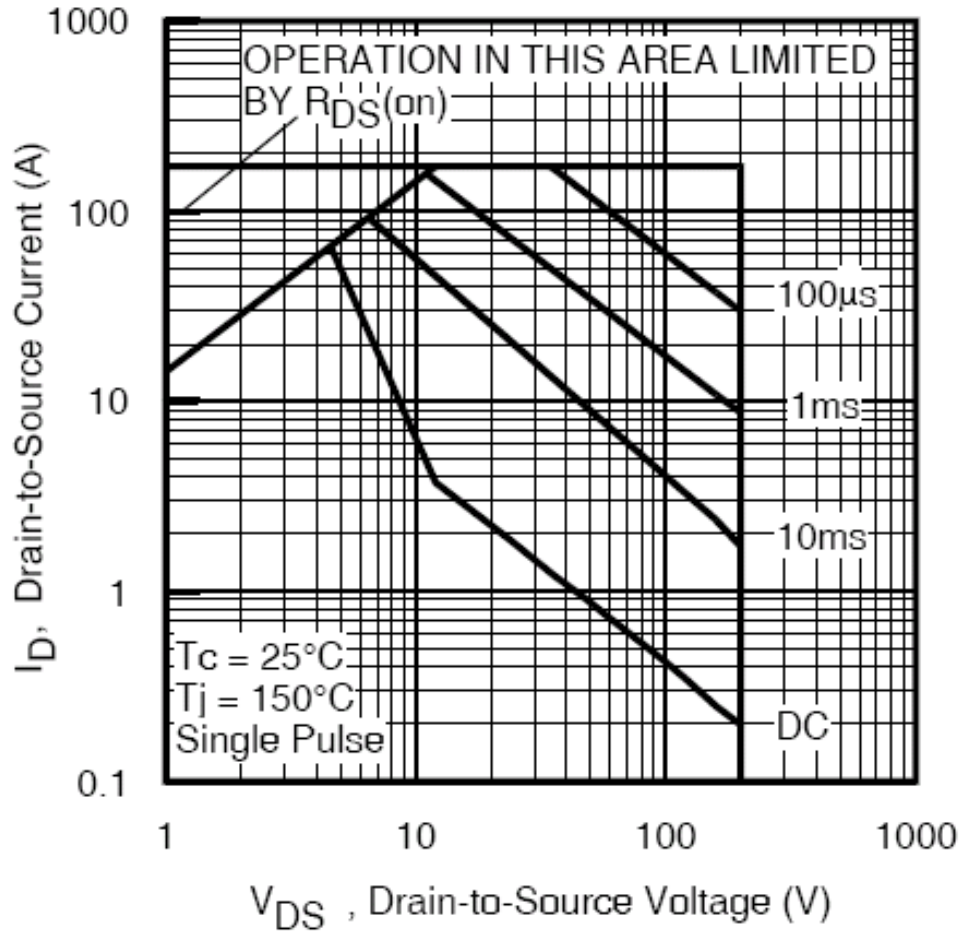


FIGURE 6. Safe operating area graph.

## 5. PACKAGING

5.1 Packaging. For acquisition purposes, the packaging requirements shall be as specified in the contract or order (see 6.2). When packaging of materiel is to be performed by DoD or in-house contractor personnel, these personnel need to contact the responsible packaging activity to ascertain packaging requirements. Packaging requirements are maintained by the Inventory Control Point's packaging activities within the Military Service or Defense Agency, or within the Military Service's system commands. Packaging data retrieval is available from the managing Military Department's or Defense Agency's automated packaging files, CD-ROM products, or by contacting the responsible packaging activity.

## 6. NOTES

(This section contains information of a general or explanatory nature that may be helpful, but is not mandatory. The notes specified in [MIL-PRF-19500](#) are applicable to this specification.)

6.1 Intended use. Semiconductors conforming to this specification are intended for original equipment design applications and logistic support of existing equipment.

6.2 Acquisition requirements. Acquisition documents should specify the following:

- a. Title, number, and date of this specification.
- b. Packaging requirements (see [5.1](#)).
- c. Lead formation and finish (see [3.4.1](#)).
- d. Product assurance level and type designator.
- e. For acquisition of RHA designated devices, [table II](#), subgroup 1 testing of group D herein is optional. If subgroup 1 is desired, it should be specified in the contract or order.
- f. If specific SEE characterization conditions are desired (see section 6.6 and [table IV](#)), manufacturer's cage code should be specified in the contract or order.
- g. If SEE testing data is desired, it should be specified in the contract or order.

6.3 Qualification. With respect to products requiring qualification, awards will be made only for products which are, at the time of award of contract, qualified for inclusion in Qualified Manufacturers List (QML 19500) whether or not such products have actually been so listed by that date. The attention of the contractors is called to these requirements, and manufacturers are urged to arrange to have the products that they propose to offer to the Federal Government tested for qualification in order that they may be eligible to be awarded contracts or orders for the products covered by this specification. Information pertaining to qualification of products may be obtained from DLA Land and Maritime, ATTN: VQE, P.O. Box 3990, Columbus, OH 43218-3990 or e-mail [vqe.chief@dla.mil](mailto:vqe.chief@dla.mil). An online listing of products qualified to this specification may be found in the Qualified Products Database (QPD) at <https://assist.dla.mil>.

6.4 Substitution information. Devices covered by this specification are substitutable for the manufacturer's and user's Part or Identifying Number (PIN). This information in no way implies that manufacturer's PIN's are suitable for the military PIN.

Preferred types Military PIN	Commercial PIN (1)
	TO254AA
2N7431 2N7432 2N7433	IRHM_064 IRHM_160 IRHM_260

- (1) IRHM7: 100k Rad (Si)  
 IRHM3: 300k Rad (Si)  
 IRHM4: 600k Rad (Si)  
 IRHM8: 1,000k Rad (Si)

6.5 JANC die versions. The JANHC and JANKC die versions of these devices are covered under specification sheet [MIL-PRF-19500/657](#).

6.6 Application data.

6.6.1 Manufacturer specific irradiation data. Each manufacturer qualified to this slash sheet has characterized its devices to the requirements of [MIL-STD-750](#) method 1080 and as specified herein. Since each manufacturer's characterization conditions can be different and can vary by the version of method 1080 qualified to, the [MIL-STD-750](#) method 1080 revision version date and conditions used by each manufacturer for characterization have been listed here (see [table IV](#)) for information only. SEE conditions and figures listed in section 6 are current as of the date of this specification sheet, please contact the manufacturer for the most recent conditions.

TABLE IV. Manufacturers characterization conditions.

Manufactures CAGE	Inspection	MIL-STD-750		Sample plan
		Method	Conditions	
No manufacturers are currently qualified to the SEE requirements	SEE <u>1/</u> Electrical measurements	1080	See MIL-STD-750E method 1080 $I_{GSSF1}$ , $I_{GSSR1}$ , and $I_{DSS1}$ in accordance with table I, subgroup 2	3 devices
	Electrical measurements		$I_{GSSF1}$ , $I_{GSSR1}$ , and $I_{DSS1}$ in accordance with table I, subgroup 2	
<div style="border: 1px solid black; padding: 5px; width: fit-content; margin: 0 auto;">                     Upon qualification, all manufacturers will provide the verification test conditions to be added to this table.                 </div>				

1/  $I_{GSSF1}$ ,  $I_{GSSR1}$ , and  $I_{DSS1}$  was examined before and following SEE irradiation to determine acceptability for each bias condition. Other test conditions in accordance with table I, subgroup 2, may be performed at the manufacturer's option.

6.7 Changes from previous issue. The margins of this specification are marked with asterisks to indicate where changes from the previous issue were made. This was done as a convenience only and the Government assumes no liability whatsoever for any inaccuracies in these notations. Bidders and contractors are cautioned to evaluate the requirements of this document based on the entire content irrespective of the marginal notations and relationship to the last previous issue.

Custodians:  
 Army - CR  
 Navy - EC  
 Air Force - 85  
 NASA - NA  
 DLA - CC

Preparing activity:  
 DLA - CC  
 (Project - 5961-2013-008)

NOTE: The activities listed above were interested in this document as of the date of this document. Since organizations and responsibilities can change, you should verify the currency of the information above using the ASSIST Online database at <https://assist.dla.mil/>.